IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Tetsuzo Ueda

Serial No.: 09/904,131

Filed: July 11, 2001

2001

Group Art Unit: 1765

Examiner: Matthew Song

For: LAYERED SUBSTRATES FOR EPITAXIAL PROCESSING AND DEVICE

THE COMMISSIONER FOR PATENTS AND TRADEMARKS Washington, DC 20231

Dear Sir:

 \boxtimes

Transmitted herewith is an Amendment in the above identified application.

No additional fee is required.

Applicant is entitled to small entity status under 37 CFR 1.27

Also attached:

The fee has been calculated as shown below:

The fee has been calculat	ed as shown sere				
	NO. OF CLAIMS	HIGHEST PREVIOUSLY PAID FOR	EXTRA CLAIMS	RATE	FEE
Total Claims	18	23	0	\$18.00 =	\$0.00
Independent Claims	4	7	0	\$84.00 =	\$0.00
	Multiple claims newly presented			\$0.00	
Fee for extens			on of time		\$0.00
					\$0.00
		Total of Above Calculations			\$0.00

Please charge my Deposit Account No. <u>500417</u> in the amount of \$0.00. An additional copy of this transmittal sheet is submitted herewith.

The Commissioner is hereby authorized to charge payment of any fees associated with this communication or credit any overpayment, to Deposit Account No. 500417, including any filing fees under 37 CFR 1.16 for presentation of extra claims and any patent application processing fees under 37 CFR 1.17.

Respectfully submitted,

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Date: March 17, 2003

PATENT

Docket No.: 53074-026

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Tetsuzo Ueda

Serial No.: 09/904,13

Filed: July 11, 2001

Group Art Unit: 1765

Examiner: Matthew Song

For: LAYERED SUBSTRATES FOR EPITAXIAL PROCESSING AND DEVICE

AMENDMENT

Commissioner for Patents Washington, DC 20231

Sir:

In response to the Office Action dated January 6, 2003, having a three-month shortened statutory period for response set to expire on April 6, 2003, reconsideration of the above-identified application is respectfully requested in view of the following amendment and remarks.

IN THE CLAIMS

Please amend claims 11, 12, 15, 18 and 19 to read as follows:

11. An epitaxial growth method comprising:

growing an epitaxial layer on a layered substrate which exhibits bowing, wherein the layered substrate has at least two layers, wherein at least two of the layers have different thermal coefficients.

12. The epitaxial growth method of claim 11 further comprising the step of selective etching a portion of the epitaxial layer.